

**INFORMATION DISCLOSURE STATEMENT**

Applicant : Masuda et al.  
App. No : 10/568,126  
Filed : February 14, 2006  
For : POSITIVE PHOTORESIST  
COMPOSITION AND RESIST  
PATTERN FORMATION  
Examiner : Chu, J.  
Art Unit : 1795  
Conf No. : 1055

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 2 (two) references, of which 1 (one) is enclosed/submitted.

This Information Disclosure Statement is being filed after the mailing date of a final action or after the mailing date of a Notice of Allowance. This Statement is accompanied by the fee set forth in 37 C.F.R. § 1.17(p). The Commissioner is hereby authorized to charge any additional fees which may be required or to credit any overpayment to Account No. 11-1410.

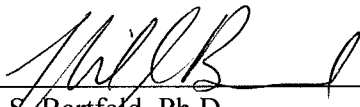
CERTIFICATION UNDER 37 C.F.R. § 1.97(e)(1)

I hereby certify that each item of information contained in this Statement was first cited in any communication from a foreign Patent Office in a counterpart foreign application not more than three months prior to the filing of this Information Disclosure Statement.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 3/25/10

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